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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/719,926	11/21/2003	Yuji Takaoka	09792909-5767	3342	
26263 7	26263 7590 02/07/2006			EXAMINER	
SONNENSC	HEIN NATH & ROS	BRYANT, E	BRYANT, DELORIS S		
P.O. BOX 061080 WACKER DRIVE STATION, SEARS TOWER CHICAGO, IL 60606-1080			ART UNIT	PAPER NUMBER	
			2813		

DATE MAILED: 02/07/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)		
Office Action Commence	10/719,926	TAKAOKA ET AL.		
Office Action Summary	Examiner	Art Unit		
	Deloris Bryant	2813		
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address -		
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period of - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tim vill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONEI	lely filed the mailing date of this communication. O (35 U.S.C. § 133).		
Status				
1) Responsive to communication(s) filed on 14 No	ovember 200 <u>5</u> .			
2a) This action is <b>FINAL</b> . 2b) ▼ This	action is non-final.			
3) Since this application is in condition for allowar	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is			
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	33 O.G. 213.		
Disposition of Claims				
4) ☐ Claim(s) 17-21 is/are pending in the application 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 17-21 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/o	vn from consideration.			
Application Papers				
9)☐ The specification is objected to by the Examine 10)☒ The drawing(s) filed on 21 November 2003 is/a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11)☐ The oath or declaration is objected to by the Ex	re: a)⊠ accepted or b)⊡ objector drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).		
Priority under 35 U.S.C. § 119				
<ul> <li>12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents</li> <li>2. Certified copies of the priority documents</li> <li>3. Copies of the certified copies of the priority documents</li> <li>* See the attached detailed Office action for a list</li> </ul>	s have been received. s have been received in Application rity documents have been received (PCT Rule 17.2(a)).	on No ed in this National Stage		
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:			

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#### **DETAILED ACTION**

Applicant's response to advisory action dated November 29, 2005 and subsequent RCE filing dated December 12, 2005 is hereby acknowledged.

# Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:

- 1. Determining the scope and contents of the prior art.
- 2. Ascertaining the differences between the prior art and the claims at issue.
- 3. Resolving the level of ordinary skill in the pertinent art.
- 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

Claim 17-18 and 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Eichelberger (US 6,159,767) in view of Borwick, III et al (US 2004/0227201) in further view of Nakamura et al (US 2003/0006441). Eichelberger discloses a method of fabrication of a

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semiconductor device, comprising the steps of: die bonding of a plurality of semiconductor chips [12] on a substrate [14,Fig. 1]; forming of a first insulation film [16] on said substrate, wherein a top surface and at least a portion of side surfaces of said plurality of semiconductor chips are incrusted in said insulation film [16, see Fig. 1] and wherein each said semiconductor chip is set so as to float on an adhesive resin applied on said substrate (Fig. 1). Eichelberger, however, does not teach forming a target mark in the substrate nor does he teach forming a second or third insulation film whereby the second insulation film is flatly grounded. Eichelberger also does not teach forming a connection hole through the first, second and third insulation film or the forming of wiring on the third insulation film. Borwick, III, however, does teach forming an alignment mark (Fig. 2, 55) in the substrate. Furthermore, Nakamura teaches multiple layers of insulating film (Fig. 1, 11a-d) whereby the insulating film 11c is flattened (pg. 8, para, 0169). Nakamura also teaches forming a connection hole through the insulating film 11a-11d and also the forming of wiring (Fig. 1, 14a-14c) that is electrically connected with the lower region of the semiconductor device (pg. 8, para. 0178). Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify the method of Eichelberger with the teaching of Borwick, III and Nakamura. One would have been motivated to so modify Eichelberger for the benefit having alignment marks in the substrate to allow for precise vertical alignment of all upper layers of the structure (Borwick, III; pg. 2, para. 0029) and having multiple layers of insulating film with increasing etching selection ratio between each layer to allow the connection hole to be patterned in a controlled manner (Nakamura; pg. 8, para 0171).

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Claim 19 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Eichelberger in view of Borwick, III et al (US 2004/0227201) and Nakamura et al (US 2003/0006441) in further view of Hudak et al (5,656,552). Eichelberger, Borwick and Nakamura do not teach a substrate comprising a silicon wafer. However, Hudak does teach that a "substrate may be a rigid material such as ceramic or semiconductor". Silicon is a well-known semiconductor used throughout the art. Further Eichelberger, Borwick and Nakamura do not teach the removal of said substrate [Fig. 1]. Hudak, however, does teach the removal of said substrate [Fig. 8-9, col. 7, lns 63-67 and col. 8, lns 1-10]. Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to form a multi-chip semiconductor that is substrateless. One would have been motivated to so modify Eichelberger along with the teaching of Borwick, III, Nakamura and Hudak for the benefit of allowing the semiconductor device to have flexibility in any direction [col. 8, line 47].

## Response to Arguments

Applicant's arguments with respect to claims 17-21 have been considered but are moot in view of the new ground(s) of rejection.

### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Deloris Bryant whose telephone number is (571) 272-8670. The examiner can normally be reached on M-F 7:30-4:00.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

dsb

CAPIL WHITEHEAD, JR.
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800